# INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(PTO-1449)



| ATTY. DOCKET NO. | SERIAL NO. |
|---|---|
| 49657-274 | 09/227,935 |
| APPLICANT: Eiji HASUNUMA, et al. | |
| FILING DATE: January 11, 1999 | GROUP: 2811 |

## U.S. PATENT DOCUMENTS

| EXAMINER'S INITIALS | PATENT NO. | DATE | NAME | CLASS | SUBCLASS | FILING DATE |
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## FOREIGN PATENT DOCUMENTS

| EXAMINER'S INITIALS | PATENT NO. | DATE | COUNTRY | CLASS | SUBCLASS | Translation Yes | Translation No |
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| Loke | 4442652 A1 | 01/25/1996 | German(w/English Abstract) | | | | ✓ |
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## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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| Loke | Novel Selective Epi Base for double-poly Structures. In: IBM Technical Disclosures Bulletin, 1992, Vol. 35, Pages 51 - 53 |
| Loke | PFIESTER, J.R.,; SIVAN, R.D.; GUNDERSON, C.D.; CRAIN, N.E. (et al.): An ITLDD CMOS Process with Self-Aligned Reverse-Sequence LDD/Channel Implantation. In: IEEE Transactions on electron devices. ISSN 0018-9383. 1991, Vol. 38, No. 11, Pages 2460 - 2464 |
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| EXAMINER | DATE CONSIDERED |
|---|---|
| Loke | 5/21/02 |

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.